

Title (en)  
METHOD FOR REDUCING GLARE AND CREATING MATTE FINISH OF CONTROLLED DENSITY ON A SILICON SURFACE

Title (de)  
VERFAHREN ZUR BLENDUNGSMINDERUNG UND ERZEUGUNG EINES MATTE FINISH GESTEUERTER DICHTS AUF EINER SILIZIUMOBERFLÄCHE

Title (fr)  
PROCEDE DE REDUCTION D'EBLOUISSEMENT ET DE CREATION DE FINI MAT DE DENSITE COMMANDEE SUR UNE SURFACE DE SILICIUM

Publication  
**EP 1664976 A4 20100224 (EN)**

Application  
**EP 04809720 A 20040909**

Priority  
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• US 50140003 P 20030910

Abstract (en)  
[origin: WO2005026910A2] ABSTRACT OF THE DISCLOSURE [0027] A system (100) and method for producing a matte finish on a silicon surgical blade or other surface, wherein the system comprises a computer (2), laser and lens assembly (8), and an x-y coordinate controller (6) which controls the position of the laser in accordance with received instructions. The method comprises creating a design or pattern (200) to be ablated on the surgical blade by the laser (8). A data set is then generated from file representing the design or pattern, and the data set instructions are sent to the x-y coordinate controller (6) and laser and lens assembly (8). The x-y coordinate controller (6) moves the laser (8) to a location where a crater (212, 214) is to be formed, and the laser illuminates the surgical blade, burning a pit or crater of pre-determined diameter, depth and spacing into the surgical blade. The process then rapidly repeats itself until the design or pattern has been created in the surgical blade (10).

IPC 8 full level  
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Citation (search report)  
• [X] US 5579583 A 19961203 - MEHREGANY MEHRAN [US], et al  
• See references of WO 2005026910A2

Cited by  
CN105643101A

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